Page 1 of 3 Application No. Applicant(s) PTO-1449 OCT 1 5 2004 10/696,326 Zhang et al. Information Disclosure Citatis Docket Number Group Art Unit Filing Date in an Application ரும் 10/29/2003 064441.0266 1756 **U.S. PATENT DOCUMENTS** DOCUMENT NO. DATE NAME CLASS SUBCLASS **FILING DATE** NE 12/23/75 Pohl et al. 355 132 07/01/74 3927943 06/28/77 Oscarsson et al. 355 91 05/03/76 4032233 C. 4131363 12/26/78 75 Shea et al. 355 12/05/77 D. 06/26/79 de Masi 355 79 11/14/77 4159176 E. 4255216 03/10/81 Conant et al. 156 80 01/14/80 F. 09/11/84 Yen 206 334 08/19/83 4470508 G. 4536240 08/20/85 Winn 156 74 02/22/83 H. 4584216 04/22/86 Kenworthy et al. 428 38 06/15/84 1. 04/14/87 Fukumitsu et al. 428 215 06/13/85 4657805 J. 4737387 04/12/88 Yen 428 14 07/07/86 K. 4833051 05/23/89 5 **imamura** 430 12/17/87 L. 08/14/90 Squire 526 247 12/28/89 4948851 M. 11/27/90 Squire 350 409 04/09/90 4973142 N. 428 506 12/06/98 04/16/91 Hong 5008156 5061024 10/29/91 Keys 359 350 09/06/89 **FOREIGN PATENT DOCUMENTS** TRANSLATION DOCUMENT NO. DATE COUNTRY CLASS SUBCLASS YES NO 2000292909 10/20/00 G03F 1/14 JP (abstract only) X 10062966 03/06/98 G03F 1/14 JP (abstract only) **NON-PATENT DOCUMENTS**

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